TechniEtch CN10

(Manufacturer of this Product: Technic France)

Copper Etch

Technical Data Sheet



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General Information

TechniEtch CN10 is intended for etching of Copper and Nickel

Etch Rate and Operation Conditions

The setup of TechniEtch CN10 should be done with the addition of 8 ... 16% $H_2O_{2\;(30\%)}$, prior to the etching process. At 25°C the etch rate is about 0.3 ... 0.4 µm per minute for Cu and also in the same range for Ni.

Without the addition of $H_2O_{2\;(30\%)}$ the etch rate is not zero, but lower and could be less homogenous.

Tank immersion and application in spray etching machines are possible. Rinsing in DI-water finalizes the etching process.

Storage

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Storage in well-closed containments at 0-35°C recommended.